

ISSUE CLASSIFICATION	
Class	Subclass

PATENT NUMB

U.S. UTILITY Patent Application

<p> </p> <p> O.P.E. SCANNED Q.A. <u>A.G.</u> </p>	<p>PATENT DATE</p>
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APPLICATION NO. 09/731264	CONT/PRIOR	CLASS 438 26	SUBCLASS 05	ART UNIT 2842 -1765	EXAMINER Deo-Hill
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APPLICANTS

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Thomas Osterheld
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TITLE

Multi-step polish process to control uniformity when using a selective slurry on patterned wafers

PTO-2040
12/89

ISSUING CLASSIFICATION

ISSUING CLASSIFICATION									
ORIGINAL				CROSS REFERENCE(S)					
CLASS		SUBCLASS		CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)				
INTERNATIONAL CLASSIFICATION									

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<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____ _____ _____	_____ (Primary Examiner) (Date)			ISSUE FEE	
				Amount Due	Date Paid
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner) (Date)			ISSUE BATCH NUMBER	

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